

TSMC-01-1094

January 14, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/694,426 10/27/03 |

Fei-Gwo Tsai et al.

METHOD OF A FLOATING PATTERN
LOADING SYSTEM IN MASK DRY-ETCHING
CRITICAL DIMENSION CONTROL

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.


The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on January 27, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 1/27/04

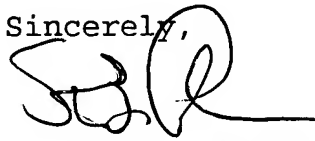
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U.S. Patent 6,281,049 to Lee, "Semiconductor Device Mask and Method for Forming the Same," discloses a mask process with dummy patterns involving macro loading.

U.S. Patent 5,899,706 to Kluwe et al., "Method of Reducing Loading Variation During Etch Processing," discloses a process to reduce loading variation during etching.

U.S. Patent 5,278,105 to Eden et al., "Semiconductor Device with Dummy Features in Active Layers," discloses a method for a device with dummy lines in active layers.

Sincerely,

A handwritten signature in black ink, appearing to be 'SBA', written over the word 'Sincerely,'.

Stephen B. Ackerman,
Reg. No. 37761

(Use several sheets if necessary)

Agitation Number

10/694,426

Fei-Gwo Tsaï et al.

10/27/03

Group 1st Unit

DATE COMPLETED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.